

FORM PTO-1449	SERIAL NO. Not Yet Assigned	CASE NO. 9905/26 (BIF023238/US)
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	FILING DATE Herewith	GROUP ART UNIT Not Yet Assigned
APPLICANTS: FOURNEL et al.		

## REFERENCE DESIGNATION

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
	A1	5,131,968	07/21/1992	Wells et al.	=====	=====
	A2	4,832,253	05/23/1989	Kloucek et al.	=====	=====

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES OR NO
	A3	FR 2 789 518 A1	08/11/2000	France	X	
	A4	EP 0 895 282 A3	01/26/2000	EPO		
	A5	EP 0 895 282 A2	02/03/1999	EPO		
	A6	EP 0 410 679 A1	07/24/1999	EPO		
	A7	EP 0 383 391 A1	02/12/1990	EPO		
	A8	1-169917	07/05/1999	Japan		Abstract

EXAMINER INITIAL	OTHER ART -- NON PATENT LITERATURE DOCUMENTS <small>(Include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.</small>					
	A9	Feijoo et al., "Prestressing of Bonded Wafers", Proceedings of the 1st International Symposium on Semiconductor Wafer Bonding, Science Technology and Applications, Vol. 92-7, The Electrochemical Society (1992), pp. 230-238.				
	A10	Feijoo et al., "Generalized Formula for Curvature Radius and Layer Stresses Caused by Thermal Strain in Semiconductor Multilayer Structures," Appl. Phys. 54(1), 1983, page 83.				
	A11	S. Timoshenko, "Analysis of Bi-Metal Thermostats," J. Opt. Soc. Am. 11 (1925), page 233-256.				

EXAMINER /Jeff Attergut/	DATE CONSIDERED 02/28/2008
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /J.A./